

ABSTRACT

5 Provided is a method for preparing a chromium-silicon alloy sputtering target material. The preparation method includes the following steps: (1) mixing a chromium powder and a silicon powder under a non-oxidizing atmosphere to obtain a mixed powder; (2) performing die filling, and performing vacuum hot-pressing sintering on the mixed powder obtained after the die filling; and (3) performing furnace cooling after the vacuum hot-pressing sintering is finished to obtain the chromium-silicon alloy sputtering target material.